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TI - Concentrated tetra:methyl:ammonium bromide aqueous solution containing surfactant of hydroxy:alkyne and used in the development of photoresists

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Concentrated tetramethylammonium bromide aqueous solution comprising 5 - 12 wt.% of tetramethylammonium bromide (TMAH) contains a surfactant of hydroxyalkyne of the formula:  $R_2(R_1)C(EO)_nC-C(R_1)C(EO)_nR_2$  in the amount of 0.8 - 5 parts/100 parts (by wt.) TMAH (where,  $R_1, R_2 = 1-5C$  alkyl; EO = ethylene oxide group; sum of averages of n and m are 1 - 5).

- USE: The solution is the developer concentrate to be used for the development of photoresists.

- ADVANTAGE: The hydroxyalkyne is an improved additive to the concentrate which increases the miscibility of the alcohol and TMAB, and provides the concentrate with low surface tension, improved defoaming property and good wetting characteristics.

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